



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor Application of:
Hsu, et al

Group Art Unit: 2832

Examiner: T. Nguyen

Serial No.: 09/588,788

Filed: June 6, 2000

In Response to Office Action
Dated: February 13, 2001

For: Planar Spiral Inductor Structure
Having Enhanced Q Value

Attorney Docket No.: 67,200-262

Certificate of Mailing

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Kathy BixtonDate: February 27, 2001RESPONSE TO OFFICE ACTION

Assistant Commissioner
for Patents
Washington, D.C. 20231

Dear Sir:

In response to an Office Action mailed February 13, 2001 of a restriction requirement imposed by the Examiner, the Applicants hereby elect with traverse the prosecution of Group I, method claims (claims 1-8).

The Examiner contended that in the instant case, the product, as claimed, can be made by another and materially different process such as the inductor can be made by a screening process.

The Applicants respectfully traverse the restriction requirement for the following reasons.

The present invention discloses a method for fabricating an inductor structure which can be carried out by the steps of first providing a substrate; forming over the substrate a planar spiral conductor layer to form a planar spiral conductor, wherein a successive series of spiral within the planar spiral conductor layer is formed with a variation in at least one of: a series of linewidths of the successive series of spirals; and a series of spacings separating the successive series of spirals.

The present invention inductor structure therefore must be formed with a variation in either a series of linewidths of the successive series of spirals or a series of spacings separating the

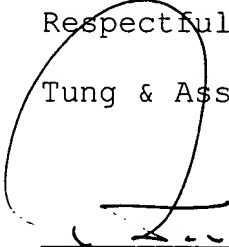
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successive series of spirals. The present invention inductor structure therefore cannot be fabricated by a screening process as suggested by the Examiner.

Based on the foregoing, the Applicants respectfully request that the restriction requirement imposed by the Examiner be withdrawn and that Group II claims, i.e. claims 9-15, be examined along with the method claims 1-8. Such favorable action by the Examiner is respectfully solicited.

Respectfully submitted,

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